



Session Title:	[ThA1] Al-rich AlGaN
Session Date:	July 16 (Thu.), 2026
Session Time:	08:30-09:45
Session Room:	Room A (Baekrok Hall B-1, 1F)
Session Chairs	

[ThA1-1] 08:30-08:45

Interface Engineering on Enhancement-Mode Al-Rich $Al_{0.8}Ga_{0.2}N$ MOSFET Enabled by Atomic Layer Etching

Tingang Liu, Haicheng Cao, Mingtao Nong, and Xiaohang Li, King Abdullah University of Science and Technology, Saudi Arabia

[ThA1-2] 08:45-09:00

Impact of AlN/AlGaN Superlattice Structure on Proton-Induced Transport in Al-Rich AlGaN Channel HEMTs from Room Temperature to 500 °C

Shyam Mohan, Joocheol Jeong, Jaejin Heo, Hyogeun Cho, Mingoo Jo, Minyeong Kim, and Okhyun Nam, Tech University of Korea, Korea

[ThA1-3] 09:00-09:15

Formation of Low-Resistance Ohmic Contacts to Al-Rich AlGaN Using Compositionally Graded n-AlGaN

Riku Ando, Ryota Akaike, Shozabro Tanaka, Hiroki Yasunaga, Takao Nakamura, and Hideto Miyake, Mie University, Japan

[ThA1-4] 09:15-09:30

Investigation of Low-Resistivity Au-Free Metal Contact on n-Type $Al_xGa_{1-x}N$ ($x \geq 0.8$)

Tingang Liu, Haicheng Cao, Mingtao Nong, and Xiaohang Li, King Abdullah University of Science and Technology, Saudi Arabia

[ThA1-5] 09:30-09:45

High-Temperature and Radiation Responses of Al-Rich AlGaN Channel HEMTs Employing Various Gate Metals

Mingoo Jo¹, Joocheol Jeong¹, Shyam Mohan¹, Jaejin Heo¹, Hyogeun Cho¹, Minyeong Kim¹, Dongseok Kim², Jiun Oh³, Minji Kim³, and Okhyun Nam¹, ¹Tech University of Korea, Korea, ²Korea Atomic Energy Research Institute, Korea, ³Korea Institute of Energy Technology, Korea